

PVD 75™

Thin Film Deposition System



Kurt J. Lesker®
Company

PROCESS EQUIPMENT™
DIVISION

Applications

- Designed for university, industrial, and government lab R&D thin film deposition
- OLED/PLED and organic electronics applications
- Photovoltaics and semiconductor devices
- Optics and decorative coatings
- Small batch production

Features

- Fully enclosed “zero” clean room footprint or optional open frame design
- D-shape 304 stainless steel chamber with aluminum door and large viewport
- Manual touch-screen or recipe-controlled, PC based process automation
- Turbomolecular or optional cryogenic high vacuum pumping

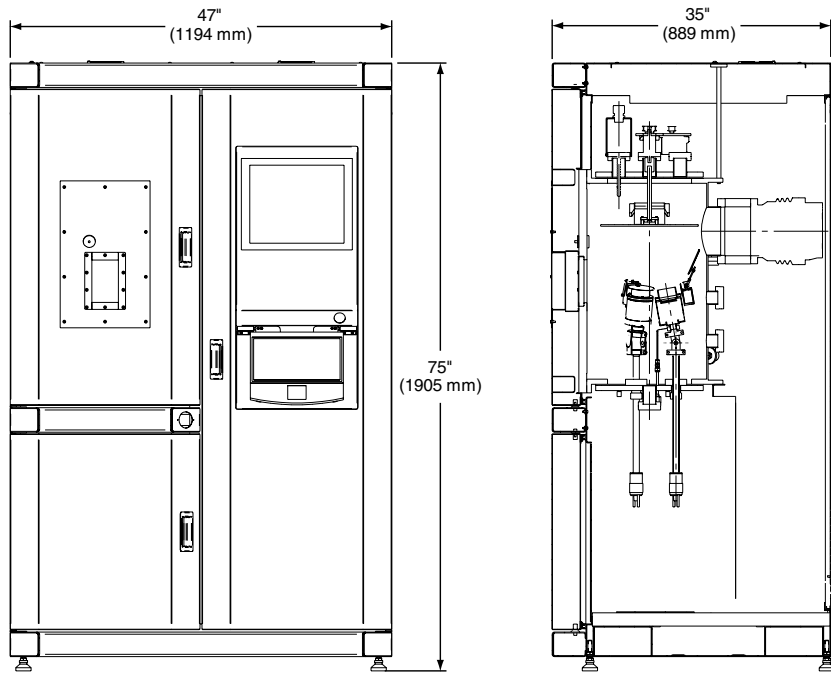
Process Modules

- Magnetron sputtering: RF, DC, Pulsed DC
- Electron beam evaporation
- Thermal evaporation
- Organic materials evaporation
- Ion source substrate cleaning or assisted deposition

Options

- Substrate heating, cooling, or biasing
- Planetary substrate fixturing
- Upstream or downstream pressure control
- Film thickness control
- Substrate load lock
- On-site installation and training

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Dimensions Approximate

Specifications

| | |
|---|--|
| Process Chamber Volume | 75 liters |
| Process Chamber Geometry | D-Shaped, 14" (365mm) wide X 14" deep (365mm) X 24" (610mm) high |
| Process Chamber Construction | 304L Stainless Steel with 6061 Aluminum Hinged Door |
| Cabinet Construction | Carbon Steel, Fully Enclosed, Gray Powder Coat Finish |
| Deposition Sources (Available in various combinations) | Torus® Magnetron Sputtering Cathode |
| | 4-Pocket 8cc Electron Beam Source |
| | Multiple Boat Source Thermal Evaporation |
| | LTE Organic Material Evaporation Source |
| Deposition Orientation | Sputter Up or Down, Evaporation Up |
| Substrate Cleaning | Ion Source or RF Bias |
| Substrate Size (max) | Single 12" (300mm) with optional 20 RPM max variable rotation |
| Substrate Heating | Quartz Lamp or Resistive Element |
| Standard Vacuum Pumping | 260 l/sec Turbo Pump, Optional 685 l/sec Turbo Pump, or 1500 l/sec Cryo Pump Available |
| Gauging | Wide Range Vacuum Gauge |
| Base Pressure Turbo Pump (CDE) | 5×10^{-7} Torr (6.7×10^{-7} mbar) |
| Process Gas | 2 Channel Manual with Optional Mass Flow Control with Pressure Control |
| System Control | PC-Based HMI, with optional Recipe Control and Datalogging |
| Required Power (typical, based on options) | 208VAC, 3Ø, 50/60 Hz; Optional 380VAC, 3Ø, 50/60 Hz |
| Available Certifications, Markings | CE and CSA |
| Warranty | 12 months upon shipment |
| Overall Dimensions (approx) | 47" (1194mm) wide X 35" (889mm) deep X 75" (1905mm) high |
| Weight (approx) | 1,800 lbs (816 kg) |

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